

ICS 19.020

CCS N 04



**NATIONAL STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

GB/T 27760-2011

**Test method for calibrating the z-magnification of an atomic
force microscope at sub-nanometer displacement levels using
si (111) monatomic steps**

利用Si(111)晶面原子台阶对原子力显微镜亚纳米高度测量进行校准的方法

(English Translation)

Issued on: December 30, 2011

Implemented on: May 1, 2012

Issued by: Standardization Administration of China

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What this standard covers

This standard specifies the use of Si (111) crystal surface atomic step height z atomic force microscope sample calibration to standard measurement method. This standard applies to work under atmospheric or vacuum atomic force microscope, and the z order to achieve maximum magnification, ie z displacement in the nanometer and sub-nanometer range, which is the atomic force microscope is used to detect the semiconductor surface, optical devices surfaces and other high-tech component surface frequently used detection range. This standard does not indicate that all possible security problems in the application of this standard, the user has the responsibility to take appropriate safety and health practices and to ensure compliance with the relevant regulations of the condition.

Document data

International classification (ICS): 19.020.

Chinese classification (CCS): N04.

Estimated length of the Chinese original: 14,185 words.

Adopted international standard: ASTM E2530-2006, MOD.

Standards quoted by this document

ISO 25178-6-2010; ISO/IEC GUID 98-3-2008; ISO/TS 21748-2004